

Title (en)

PHOTODEGRADATION-RESISTANT ELECTRODEPOSITABLE COATING COMPOSITIONS AND PROCESSES RELATED THERETO

Title (de)

PHOTODEGRADIERUNGSBESTÄNDIGE ELEKTROTAUCH-ÜBERZUGSZUSAMMENSETZUNGEN SOWIE VERFAHREN DIE SICH DARAUF BEZIEHEN

Title (fr)

COMPOSITIONS DE REVETEMENT APPLICABLE PAR ELECTRODEPOSITION RESISTANT A LA PHOTODEGRADATION ET LEURS PROCEDES DE FORMATION

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Application

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Abstract (en)

[origin: WO02070613A2] The invention provides a process for coating a substrate including electrodepositing an electrodeposable composition on the substrate, heating the coated substrate to cure the coating thereon, applying over the cured electrodeposited coating one or more pigment-containing coating compositions and/or one or more pigment-free coating compositions to form a top coat thereover, and heating the coated substrate to cure the top coat. The electrodeposable composition is formed from an ungelled cationic salt group-containing resin where the salt groups are formed from pendant and/or terminal amino groups, and an at least partially blocked aliphatic polyisocyanate curing agent. Also provided is a photodegradation resistant multi-layer composite coating of a primer layer formed from the electrodeposable composition and a top coat thereover, where the composite coating exhibits substantially no interlayer delamination upon concentrated solar spectral irradiance exposure equivalent to two years outdoor weathering. The invention further provides improved processes for electrophoretically coating a substrate.

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